

## PATENT ABSTRACTS OF JAPAN

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(54) POLISHING PAD COMPRISING POLYURETHANE COMPOSITION

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a polishing pad capable of overcoming the problems of providing bad effects to smoothing processing caused by the change of the hardness (modulus) of the polishing pad by the frictional heat between the polishing pad and an article to be processed at the time of polishing, and capable of stably carrying out the smoothing processing in wide temperature range.

SOLUTION: This polishing pad is made of a polyurethane obtained from an organic polyisocyanate, a polyol and a curing agent, as a main component. The curing agent is 4,4'-methylene-bis(o-chloroaniline), and the polyol is a polytetramethylene glycol having a 500-1,600 number average molecular weight and <1.9 molecular weight distribution (weight average molecular weight/ number average molecular weight).

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